Abstract

The present invention relates to an accommodating device for accommodation and mounting of a wafer (3) for application of a fluid (9) to a top (3o) of the wafer (3) with the following features:

- a revolving ring section (4) with:
  - a) a revolving upper edge (5),
  - b) a revolving recess (6) and
  - c) a circumferential wall (7) running from the upper edge (5) to the recess (6),
- a contact plane (A) arranged within the ring section (4) for the accommodation of the wafer (3) on a contact surface (3a) of the wafer (3),

wherein the ring section (4) by means of accommodation of the wafer (3) forms with said wafer an accommodating space (8) for accommodation of the fluid (9).